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(12) **United States Design Patent**  
**Park**

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- (54) **MASK FOR LIGHT EXPOSURE**
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- (\*\*) Term: **14 Years**

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- (51) **LOC (10) Cl.** ..... **28-03**
- (52) **U.S. Cl.**  
USPC ..... **D24/209**
- (58) **Field of Classification Search**  
USPC ..... D24/133, 158, 163, 188, 200, 209–210;  
D10/57; 606/9, 33; 607/88–94;  
D29/107–110, 122  
See application file for complete search history.

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(57) **CLAIM**

The ornamental design for mask for light exposure, as shown and described.

**DESCRIPTION**

FIG. 1 is a perspective view of a mask for light exposure according to the present design;  
 FIG. 2 is a front view thereof;  
 FIG. 3 is a rear view thereof;  
 FIG. 4 is a right side view thereof;  
 FIG. 5 is a left view thereof;  
 FIG. 6 is a top view thereof;  
 FIG. 7 is a bottom view thereof; and,  
 FIG. 8 is an illustrative view of the mask in use showing the mask worn on the face of human.  
 The broken lines are included for the purpose of illustrating environmental structure and form no part of the claimed design.

**1 Claim, 8 Drawing Sheets**

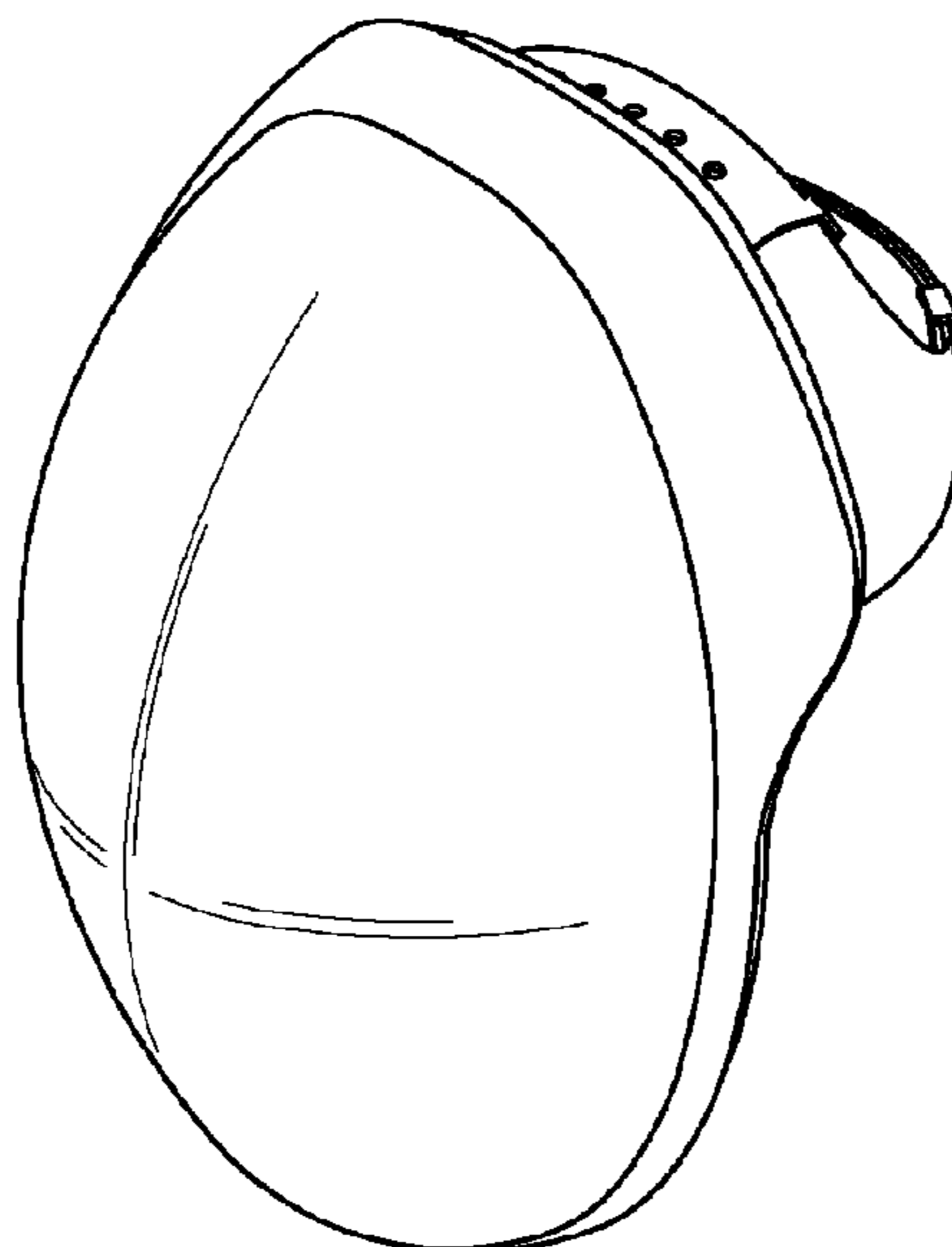


FIG. 1

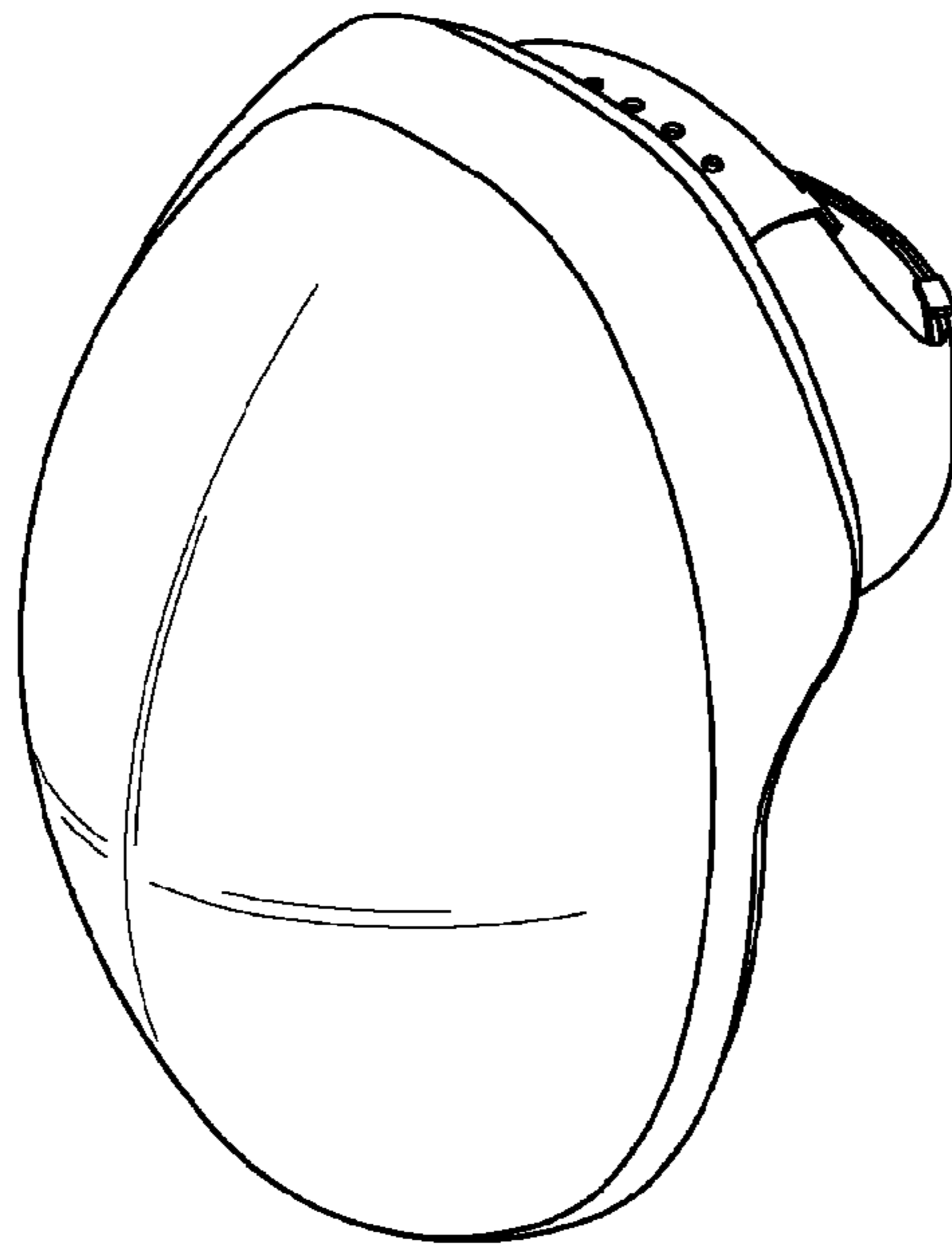


FIG. 2

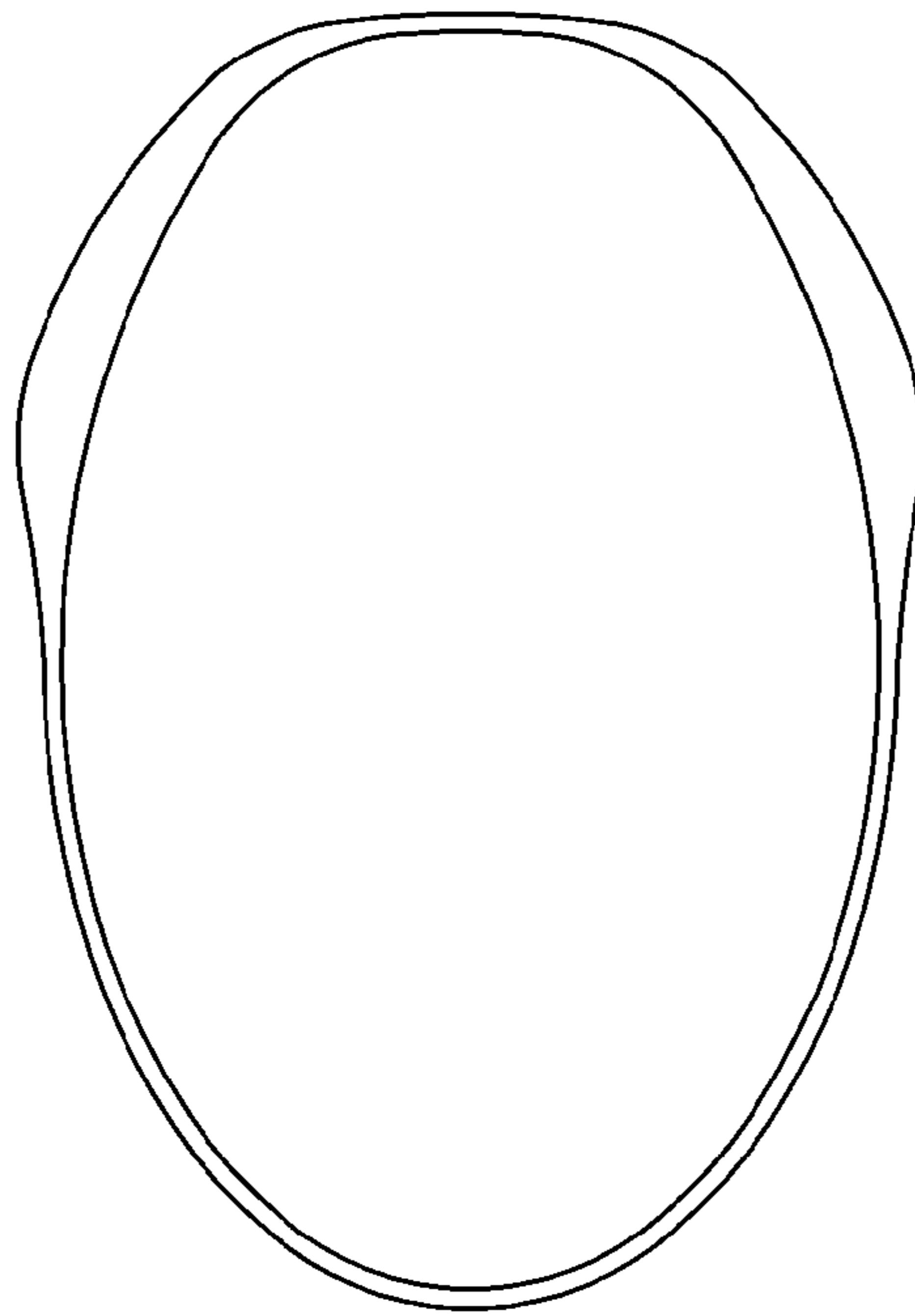


FIG. 3

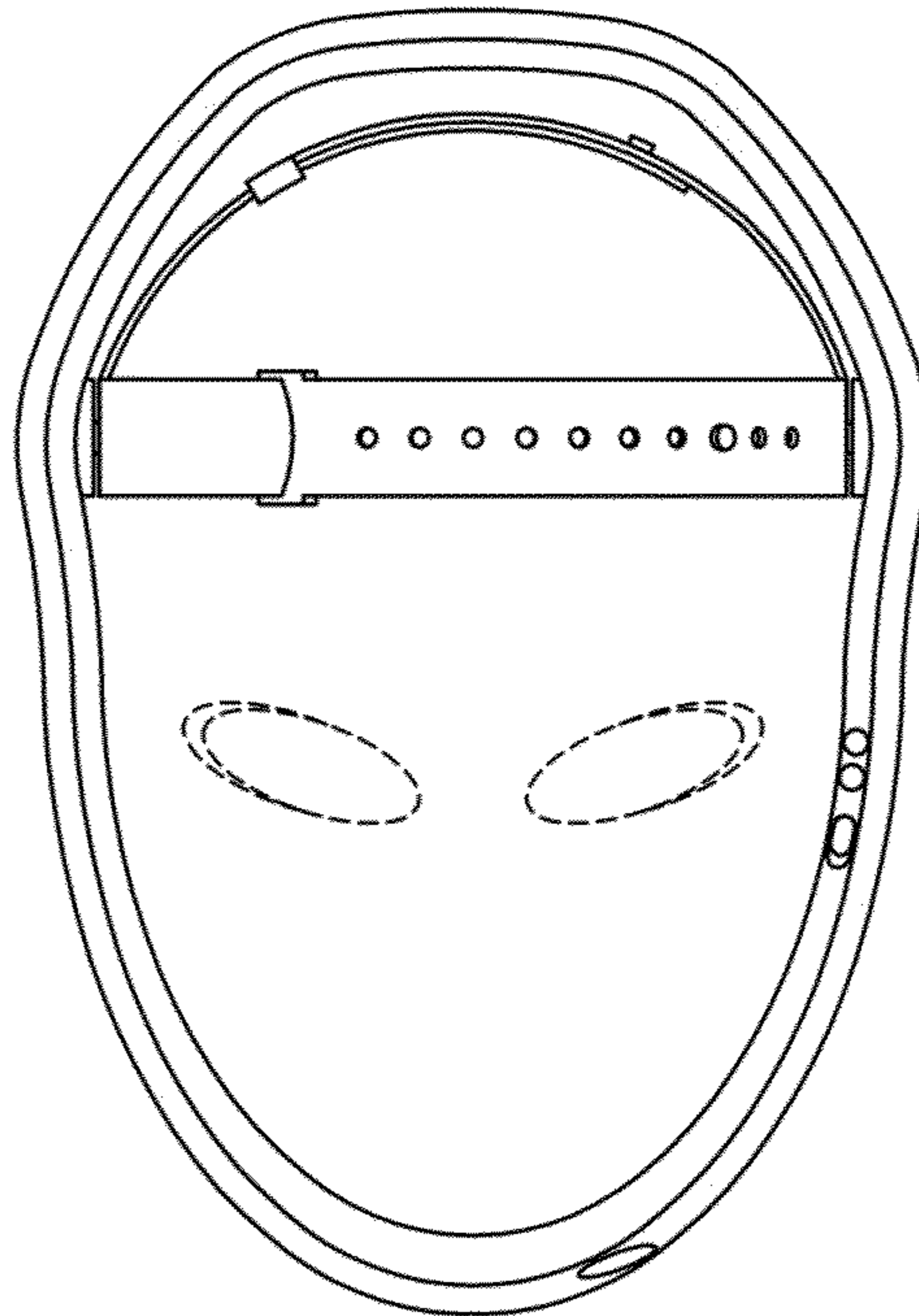


FIG. 4

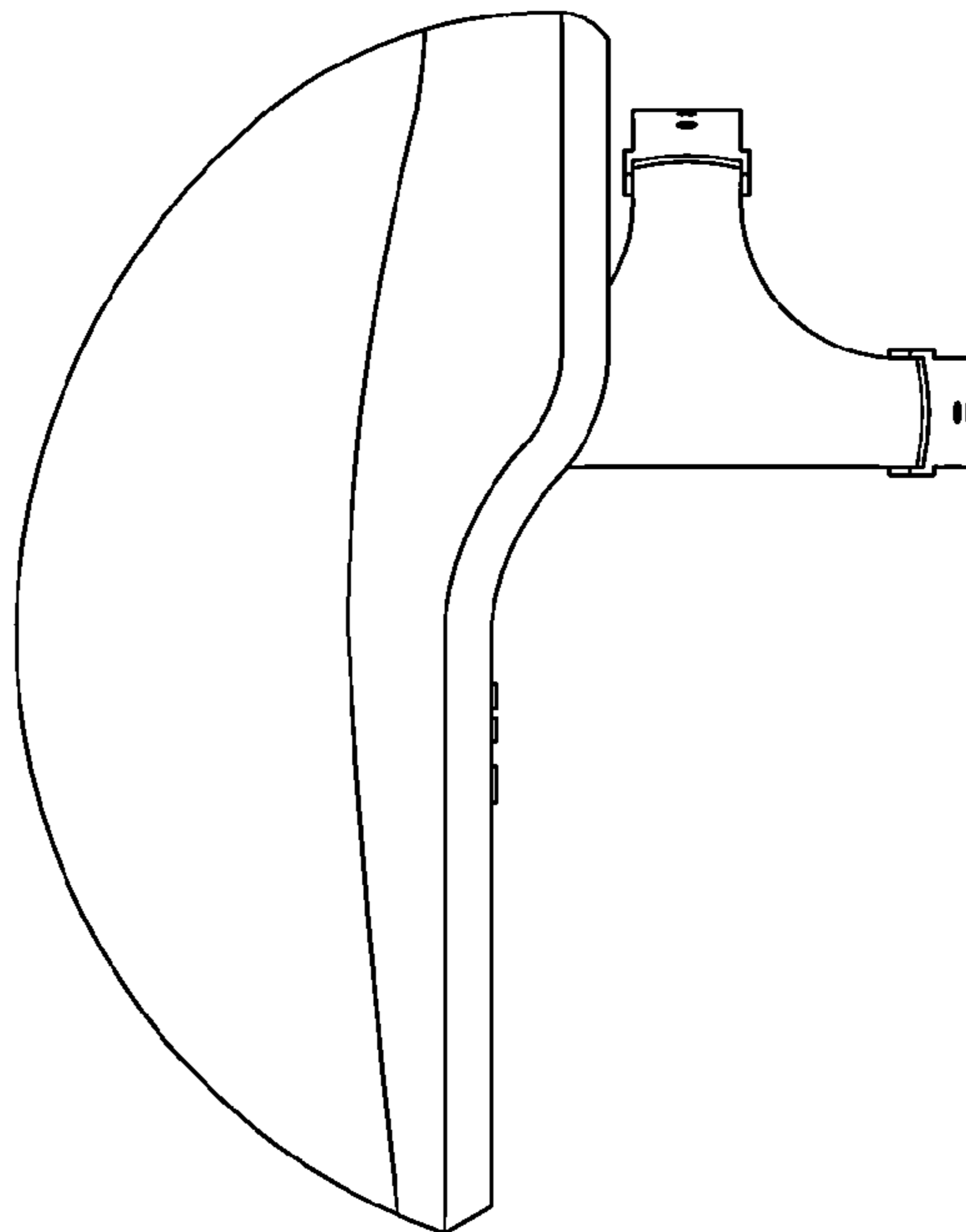


FIG. 5

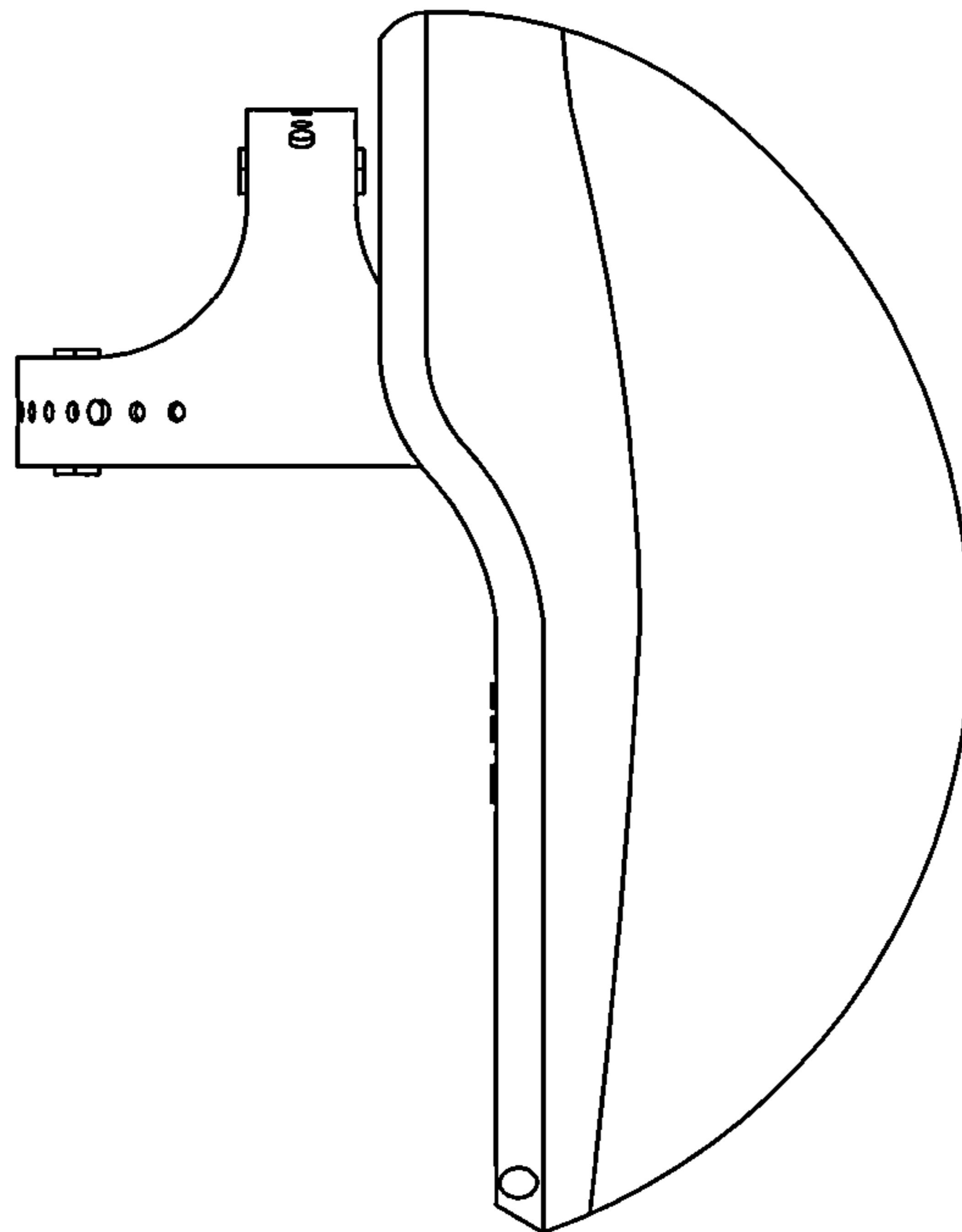


FIG. 6

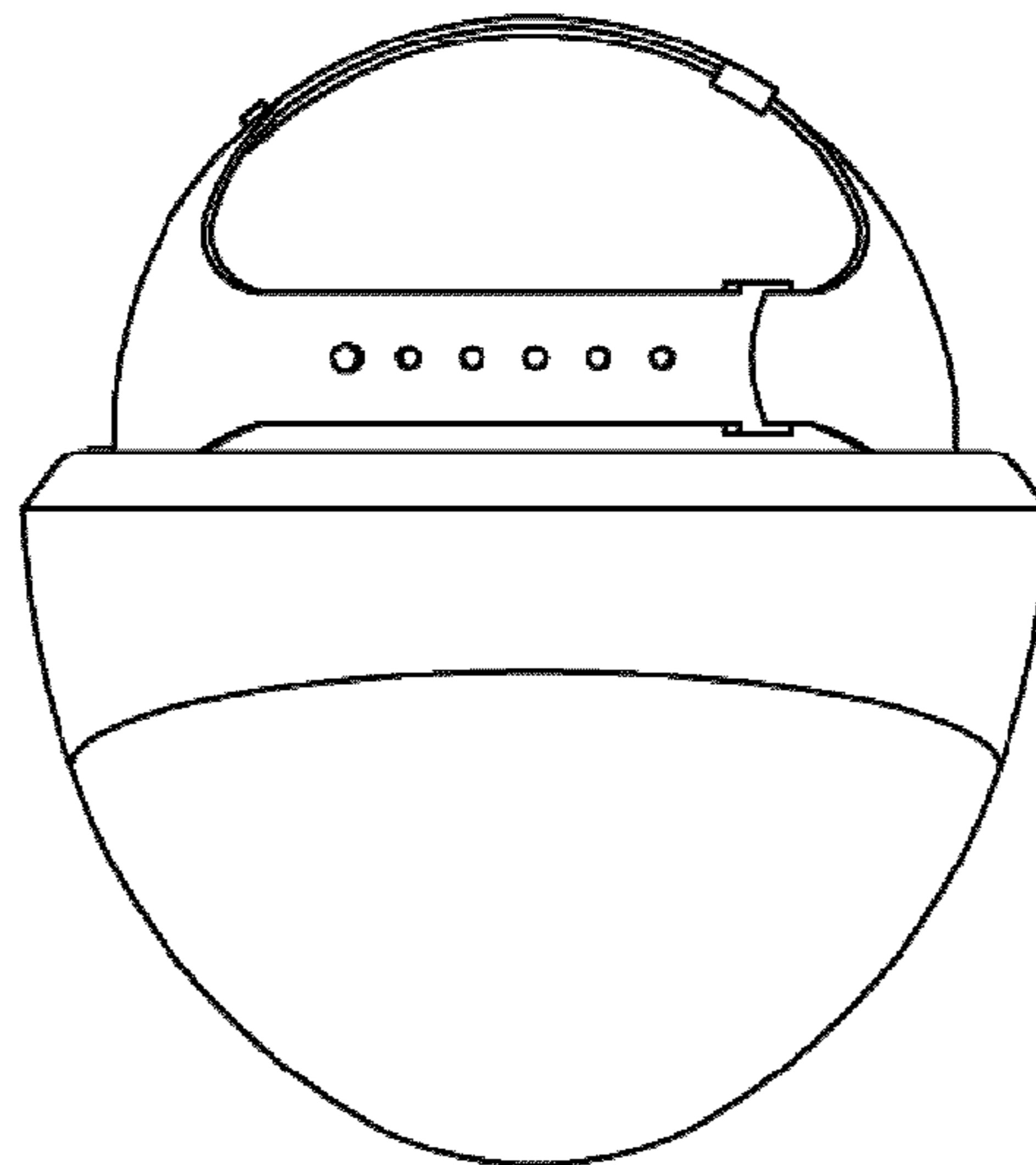


FIG. 7

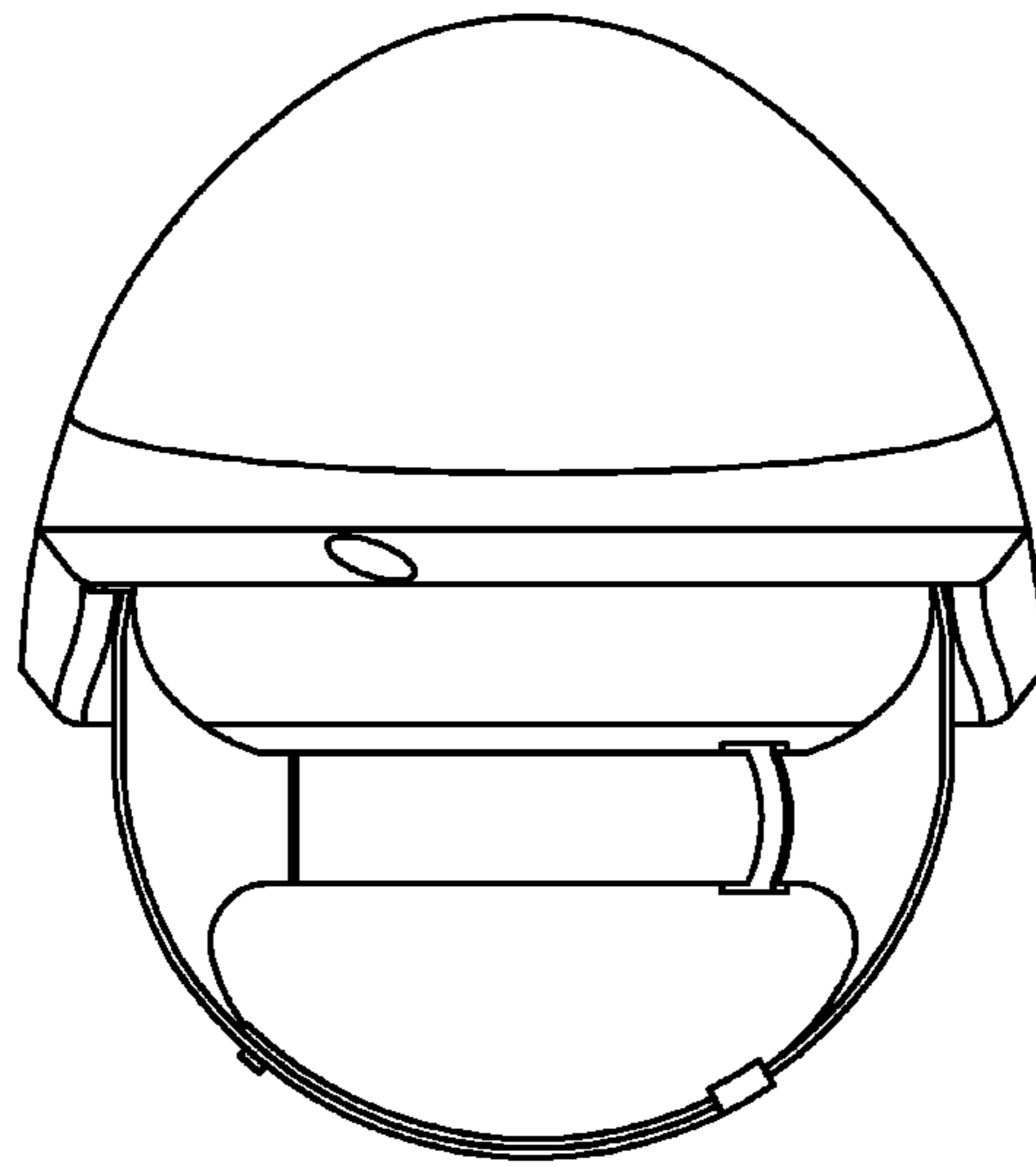




FIG. 8

